

Application No.: 10/812,354

Docket No.071469-0308969  
(FKL-020)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of: Confirmation Number: 4104

FUKIAGE, Noriaki

Application No.: 10/812,354

Group Art Unit: 1792

Filed: March 30, 2004

Examiner: TUROCY, David P.

Title: Method of Improving the Wafer to Wafer Uniformity and Defectivity of a Deposited Dielectric Film

AMENDMENT AND REQUEST FOR RECONSIDERATION

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

In response to the Non-Final Office Action dated July 14, 2008, the due date for response to which has been extended to December 14, 2008 by the attached Petition for a Two Month Extension of Time and Fee, and the Notice of Non-Compliant Amendment, dated December 3, 2008, please amend the above-identified application as follows: